

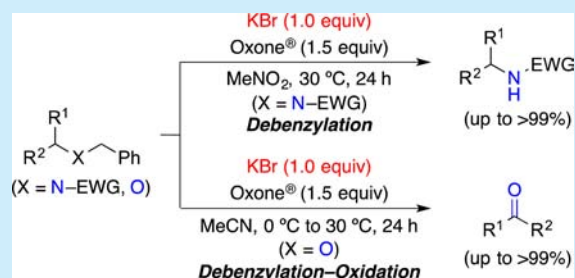
Oxidative Debenzylation of *N*-Benzyl Amides and *O*-Benzyl Ethers Using Alkali Metal Bromide

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S Supporting Information

ABSTRACT: The oxidative debenzylation of *N*-benzyl amides and *O*-benzyl ethers was promoted with high efficiency by a bromo radical formed through the oxidation of bromide from alkali metal bromide under mild conditions. This reaction provided the corresponding amides from *N*-benzyl amides and carbonyl compounds from *O*-benzyl ethers in high yields.



The benzyl group is one of the most frequently used protecting groups for amino and hydroxy functionalities in organic synthesis. The debenzylation of *N*-benzyl amines and *O*-benzyl ethers is classified into three types: (i) reductive cleavage by hydrogenolysis or single-electron transfer; (ii) acid-based cleavage with Lewis acids; (iii) oxidative cleavage with oxidants.¹ The debenzylation of *N*-benzyl amines proceeds sluggishly compared with that of *O*-benzyl ethers and thus requires harsh conditions. Moreover, the debenzylation of *N*-benzyl amides is problematic and challenging in terms of deprotection.² In previous works on the debenzylation of *O*- and *N*-benzyl derivatives, a catalytic amount of transition metals (Pd/H₂³ and Ni⁴) and a stoichiometric amount of simple metals (Li⁵ and Na⁶), Lewis acids (boron reagents,⁷ silyl reagents,⁸ and transition metal salt⁹), and oxidants (CAN,¹⁰ DDQ,^{4a,b,11} and NIS¹²) were generally required as a reaction activator. On the other hand, we have developed various oxidative transformations that involve the oxidation of bromide ion from alkali metal bromides, which are one of the most abundant natural resources on earth and feature stability in air and ease of handling, neutrality, nontoxicity, and non-elaborating products polluting the environment.¹³ We report herein the oxidative debenzylation of *N*-benzyl amides and *O*-benzyl ethers using an alkali metal halide with an oxidant under mild conditions as a novel and green-sustainable method (Figure 1).

First, we screened a series of alkali or alkaline metal bromides, oxidants, and solvents for the oxidative debenzylation of *N*-benzyl-*N*-methylbenzenesulfonamide (**1a**) and cyclododecyl benzyl ether (**3a**) (Tables S1 and S2, Supporting Information). The optimum conditions for the reaction were **1a**, KBr (1.0 equiv), and Oxone (2KHSO₅·KHSO₄·K₂SO₄) (1.5 equiv) in MeNO₂ at 30 °C, which provided *N*-methylbenzenesulfonamide (**2a**) in a quantitative yield (Scheme 1, eq 1), and **3a**, KBr (1.0 equiv), and Oxone (1.5 equiv) in MeCN at 0 to 30

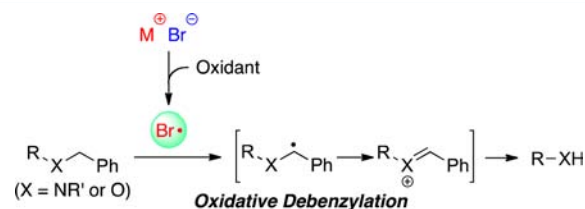
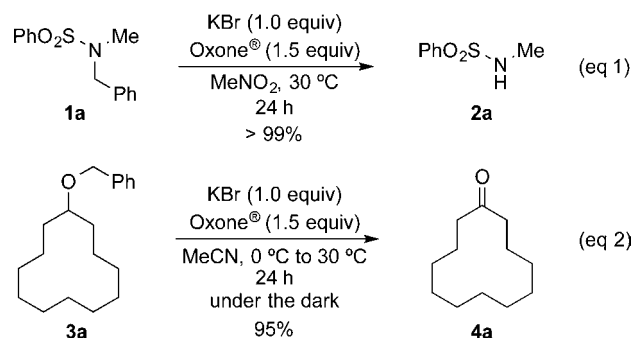


Figure 1. Debenzylation of benzyl-protected compounds using alkali metal bromide.

°C, which provided cyclododecanone (**4a**) in 95% yield but not alcohol (Scheme 1, eq 2).

It is noteworthy that the use of NBS or Br₂, the absence of KBr, and the reaction under the dark conditions were much less effective than the optimum conditions for the transformation of **1a** into **2a** (Table S1, Supporting Information).

Scheme 1. Oxidative Debenzylation of *N*-Benzyl Amide Derivative **1a and *O*-Benzyl Ether Derivative **3a****

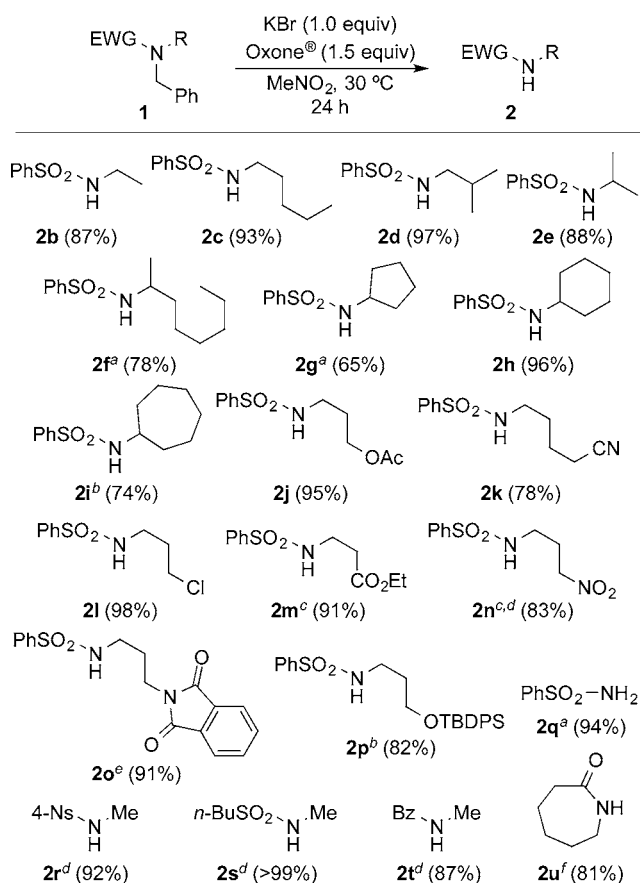


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To explore the scope of the oxidative debenylation, various *N*-benzyl amides **1** were examined using alkali metal bromide under the optimum conditions (Scheme 2). The reactions of

Scheme 2. Oxidative Debenzylation of *N*-Benzyl Amides 1 Using Alkali Metal Bromide



^aThe reaction was carried out at room temperature. ^bKBr (1.2 equiv), Oxone (1.2 equiv), and Na₂CO₃ (0.5 equiv) were used in CH₂Cl₂ at room temperature. ^cKBr (1.2 equiv) and Oxone (1.8 equiv) were used. ^dThe reaction was carried out at 50 °C. ^eKBr (1.2 equiv) and Oxone (2.0 equiv) were used. ^fThe reaction was carried out in a mixture of CH₂Cl₂/H₂O (9:1).

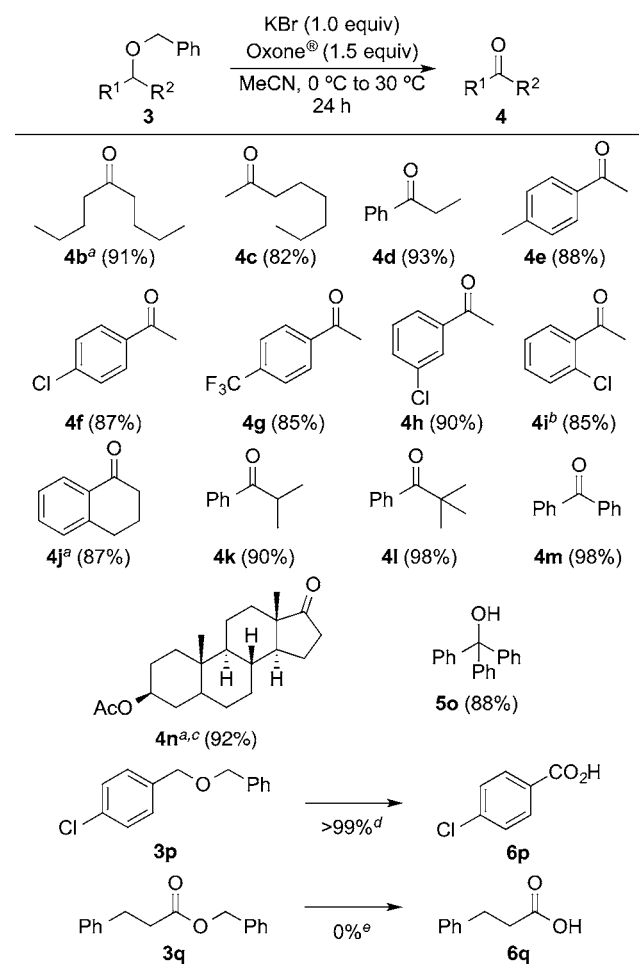
N-alkyl-*N*-benzyl benzenesulfonamides bearing Et (**1b**), *n*-pentyl (**1c**), *i*-Bu (**1d**), *i*-Pr (**1e**), and *sec*-octyl (**1f**) groups gave the corresponding debenylation products (**2b–2f**), respectively, in high yields (78–97%). *N*-Cycloalkyl-*N*-benzyl benzenesulfonamides bearing *c*-pentyl (**1g**), *c*-hexyl (**1h**), and *c*-heptyl (**1i**) groups were also converted into the desired products (**2g–2i**), respectively, in good yields (62–96%). Furthermore, various benzenesulfonamides bearing such functional groups as OAc (**1j**), CN (**1k**), Cl (**1l**), CO₂Et (**1m**), NO₂ (**1n**), and phthalimide (**1o**) provided the corresponding products (**2j–2o**), respectively, in high yields (78–98%) without degrading the functional group. The reaction of *N*-benzyl benzenesulfonamide bearing silyl ether as an orthogonal protecting group effectively converted into the desired product (**2p**) in 82% yield.

Secondary *N*-benzyl benzenesulfonamide (**1q**) was also converted into benzenesulfonamide (**2q**) in 94% yield. Other amides bearing 4-NO₂-C₆H₄SO₂ (**1r**), *n*-BuSO₂ (**1s**), PhCO (**1t**), and cyclic caproyl (**1u**) groups instead of a PhSO₂ group

were also efficiently debenzylated to form the corresponding amides (**2r–2u**) in high yields (72–>99%).

Next, we investigated a direct oxidation involving the debenylation of *O*-benzyl ethers **3** using alkali metal bromide (Scheme 3). A direct oxidation of ethers into ketones with

Scheme 3. Oxidation Involved Debenzylation of *O*-Benzyl Ethers 3 Using Alkali Metal Bromide



^aThe reaction was carried out under dark conditions. ^bOxone (1.8 equiv) was used. ^cThe reaction was carried out for 28 h. ^dKBr (2.0 equiv) and Oxone (3.0 equiv) were used. ^eBenzyl ester **3q** was recovered in 98% yield.

transition metal¹⁴ and organic oxidants has been reported.¹⁵ The present debenylation of aliphatic *O*-benzyl ethers, such as benzyl 5-nonyl ether (**3b**) and benzyl 2-octyl ether (**3c**), produced the corresponding ketones (**4b** and **4c**) in 91 and 82% yields, respectively. When a number of benzyl ethers, such as benzyl α -ethylbenzyl ether (**3d**), α -methylbenzyl ethers bearing 4-Me (**3e**), 4-Cl (**3f**), 4-CF₃ (**3g**), 3-Cl (**3h**), and 2-Cl (**3i**) on the aromatic ring, 1-benzyl-1,2,3,4-tetrahydronaphthalene (**3j**), and other benzyl ethers bearing *i*-Pr (**3k**), *t*-Bu (**3l**), and Ph (**3m**) at the α -position were used, the corresponding ketones (**4d–4m**) were also obtained in high yields (82–98%), respectively. 17 β -Benzyloxy-5 α -androstan-3 β -ol acetate (**3n**), which has a tetracyclic skeleton with an ester group, was oxidized into 3 β -acetoxy-5 α -androstan-17-one (**4n**) in 92% yield. Furthermore, triphenylmethyl benzyl ether (**3o**) classified as 3°-benzyl ether and benzyl 4-chlorobenzyl

ether (**3p**) classified as 1°-benzyl ether were also converted into 3°-alcohol **5o** and carboxylic acid **6p** in high yields, respectively. Interestingly, benzyl ester **3q** was not effective for the present oxidative debenzylation using alkali metal bromide. It was noticed that the reactions under the dark conditions for the oxidation of **3a**, **3b**, and **3j** inhibited the α -bromination of the corresponding products to give the desired ketones in high yields (Scheme S1, Supporting Information). We speculate that the effect of light for the reaction of **3** is the promotion for generation of a bromo radical to accelerate the debenzylation.

Moreover, to expand the limitation of the protecting group for the present reaction, the oxidative deprotection of *N*-protected benzenesulfonamides bearing various benzyl and allyl protecting groups (**7a–10a**) was examined using alkali metal bromide (Table 1). In particular, the use of the substrates

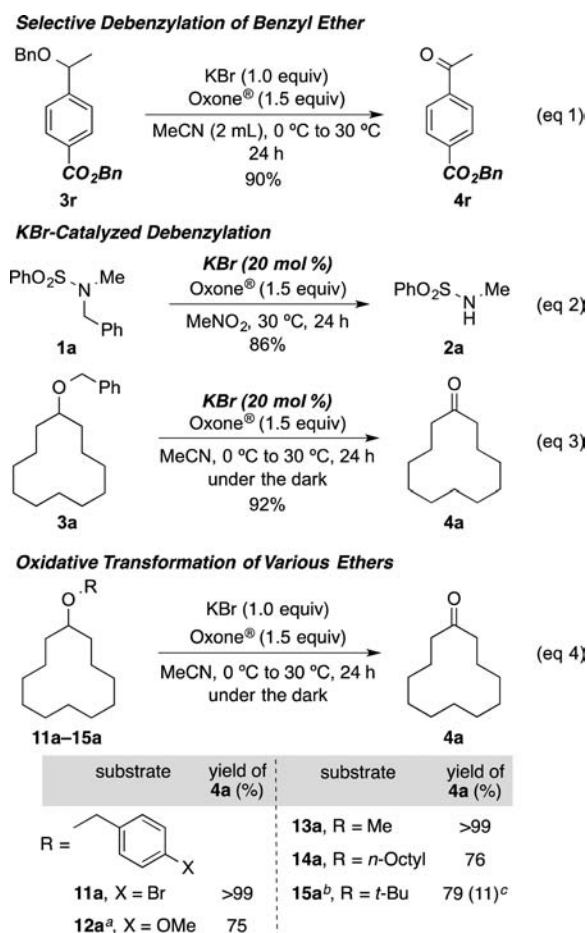
Table 1. Deprotection of *N*-Sulfonamides Bearing Various Protecting Groups

substrate	KBr (equiv)	Oxone (equiv)	conditions	yield of 2a (%)
7a	1.0	1.5	MeNO ₂ , 30 °C	93
8a	1.2	1.3	MeNO ₂ , 30 °C	88
9a	1.2	1.5	CH ₂ Cl ₂ , rt	88
10a	3.0	2.0	CH ₂ Cl ₂ /H ₂ O (9:1), rt	81

bearing *p*-methoxy benzyl (**9a**) and allyl group (**10a**) proceeded efficiently by the improvement of reaction conditions to give the desired product **2a** in high yields (88 and 81%), respectively.

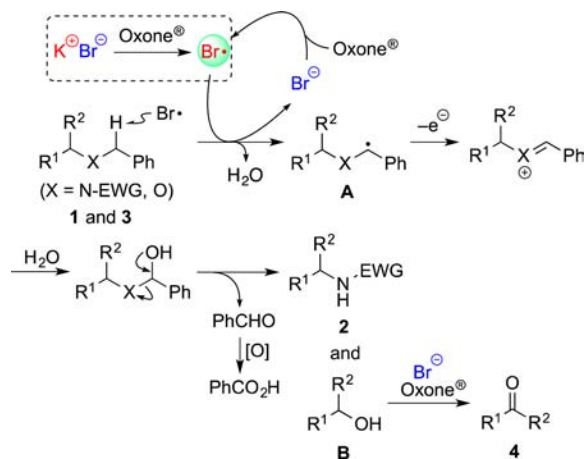
On the other hand, with regard to the functional group selectivity of the debenzylation, the selective *N*-debzilylation of *N,N'*-dibenzylamino *O*-benzyl esters bearing two kinds of benzyl groups has been reported.^{10,16} However, to the best of our knowledge, the selective *O*-debzilylation of benzyloxy benzyl ester bearing two kinds of *O*-benzyl groups has not been established. In this study, we found that the debenzylation of benzyl *p*-(α -benzyloxy)ethylbenzoate **3r** proceeded selectively to give benzyl *p*-acetylbenzoate **4r** in 90% yield (Scheme 4, eq 1). Furthermore, the alkali metal bromide-catalyzed debenzylation of **1a** and **3a** efficiently occurred to provide desired products **2a** and **4a** in 86 and 92% yields, respectively (Scheme 4, eqs 2 and 3). The present methodology with KBr/Oxone can be used for the conversion of various ethers into carbonyl compound. Indeed, not only benzyl ethers (**11a** and **12a**) but also methyl ether **13a**, *n*-octyl ether **14a**, and *t*-butyl ether **15a** were oxidized to obtain the desired ketone **4a** in high yields (75 to >99%) (Scheme 4, eq 4). We propose a reaction mechanism for the oxidative debenzylation of *N*-benzyl amides and *O*-benzyl ethers, as depicted in Scheme 5. When the oxidative debenzylation of **1a** and **3a** was carried out using alkali metal bromide, benzoic acid and/or benzaldehyde were obtained as co-products, together with the corresponding products (Scheme S2, Supporting Information). First, the bromo radical

Scheme 4. Application of Oxidative Debzilylation Using Alkali Metal Bromide



^aThe reaction was carried out with KBr (1.2 equiv) and Oxone (1.2 equiv) in ClCH₂CH₂Cl at 0 °C to room temperature. ^bThe reaction was carried out with KBr (1.2 equiv) and Oxone (1.8 equiv) for 36 h. ^cNumber in parentheses indicates the recovery of **15a**.

Scheme 5. Plausible Reaction Mechanism for the Debzilylation of Benzyl Amides and Ethers



is generated via the oxidation of bromide by Oxone in situ. The bromo radical abstracts a hydrogen atom at the benzyl position of the substrates to form benzyl radical intermediates **A**. Once **A** are formed, they are smoothly oxidized to iminium and

oxonium cations via one-electron oxidation and then hydrolyzed to produce amides **2** and alcohols **B**, respectively. In the debenzoylation of *O*-benzyl ethers, the formed debenzoylated alcohols **B** are further oxidized to carbonyl compounds **4** through the α -hydrogen atom abstraction by the bromo radical.¹⁷ For the deprotection of alkyl ethers (**13a–15a**), a bromo radical dominantly abstracts a hydrogen atom at a tertiary α -carbon atom on the substrate to proceed with alkylation.

In conclusion, we have developed an oxidative debenzoylation of *N*-benzyl amides and *O*-benzyl ethers under mild conditions by an alkali metal bromide/oxidant system. The oxidized bromo radical can be utilized in the reaction with a broad range of substrates to obtain the corresponding debenzoylated amides and carbonyl compounds in high yields. This reaction is transition-metal- and organic-reagent-free, and these reagents are stable and much less toxic. Therefore, the present method is green-sustainable as it does not yield any products that would pollute the environment. We have high hopes that the transformation via the oxidation of halides using alkali metal halides would be applicable to fine organic synthesis.

■ ASSOCIATED CONTENT

Supporting Information

Experimental procedures, spectral data, and copies of NMR spectra. This material is available free of charge via the Internet at <http://pubs.acs.org>.

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Notes

The authors declare no competing financial interest.

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